

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

the Application of: Masaki KURASAWA et al.

Group Art Unit: 2814

Serial No.: 09/960,398

Examiner: T. LE

Filed: September 24, 2001

P.T.O. Confirmation No.: 5650

CAPACITOR AND METHOD FOR FABRICATING THE SAME, AND SEMICONDUCTOR DEVICE AND METHOD FOR FABRICATING THE SAME

## PRELIMINARY AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Date: July 11, 2003

Sir:

This is a Preliminary Amendment for the above-captioned patent application. Please amend by certain as follows:

E CLAIMS:

Please amend claims 1, 3 and 14 as follows: the above-captioned patent application as follows:

## **IN THE CLAIMS**:

- 1. (Amended) A capacitor comprising:
- a buffer structure formed on a substrate;
- a lower electrode formed on the buffer structure;
- a capacitor dielectric film formed on the lower electrode, and formed of a perovskite ferroelectric material having a smaller thermal expansion coefficient than that of the buffer structure and having a crystal oriented substantially perpendicular to a surface of the lower electrode; and an upper electrode formed on the capacitor dielectric film,

